

Mass Spectrometric Analysis of Chemical Species in the Downstream Region of Ar/CF₄/H₂ Plasmas

Yuji TAMAI, Hiroshi OKUMURA, Kenji FURUYA and Akira HARATA

Department of Molecular and Material Sciences, Kyushu University, Kasuga, Fukuoka 816-8580, Japan

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The mass analysis of positive ions and neutral species was conducted in a downstream region of Ar/CF₄/H₂ plasmas. The neutral species were ionized by the attachment of the Li⁺ ion before mass-analyzing. As a result, C_nF_{2n-2} (n = 3–8), C_nF_{2n-4} (n = 3–9) and C_nF_{2n-5}⁺ (n = 5–10) appeared additionally in the Ar/CF₄/H₂ plasmas, compared to the Ar/CF₄ plasma, where C_nF_{2n+2} (n = 1–7), C_nF_{2n} (n = 4–8), C_nF_{2n+1}⁺ (n = 1–7), C_nF_{2n-1}⁺ (n = 3–7) and C_nF_{2n-3}⁺ (n = 3–9) appeared. In addition, several fluorocarbons containing hydrogen atom(s) appeared. The production of highly unsaturated neutral species is derived through the abstraction reactions of the F atom from C_mF_n by the H atom with the HF production, whereas that of highly unsaturated C_mF_n⁺ is due to different reaction mechanisms.

Keywords: plasma, CF₄, H₂, ion attachment, mass spectrometry, high-mass species

1. Introduction

Anisotropic etching of the Si wafer by mixed-gas plasmas using CF₄ and H₂ is promoted. It is believed that the film deposited on the etching wall prevents side-wall etching [1]. Controlling the kind and concentration of chemical species in the plasmas is significant for optimizing the character of the film. However, little has been known about the growth mechanisms and source species of the film. One reason is difficulty in the identification of chemical species in the plasmas, especially of high-mass neutral species.

Mass spectrometry is an appropriate method to identify chemical species included in the plasmas. It needs an ionization process. However, most of the conventional ionization methods cause fragmentation, resulting in the difficulty in their identification.

Li⁺ ion attachment mass spectrometry (IAMS) allows fragment-free detection of neutral species [2-6]. We

have recently found that various high-mass positive ions and neutral molecules with a mass number up to 400 amu are present in the downstream region of Ar/CF₄ plasmas [7]. In addition, we have clarified the growth mechanisms of the high-mass positive ions [8]. In this report, we show experimental results of the mass analysis of high-mass neutral species using IAMS in the downstream region of Ar/CF₄/H₂ plasmas, as well as positive ions. The formation mechanisms of their chemical species observed are discussed based on the enthalpy changes of the reactions.

2. Experimental Procedure

A schematic view of the experimental setup is depicted in Fig. 1. The chamber was pumped by a 550 l·s⁻¹ turbomolecular pump. An inductively coupled plasma was generated in a quartz tube with a 50 mm inside diameter by supplying a radio-frequency (RF,

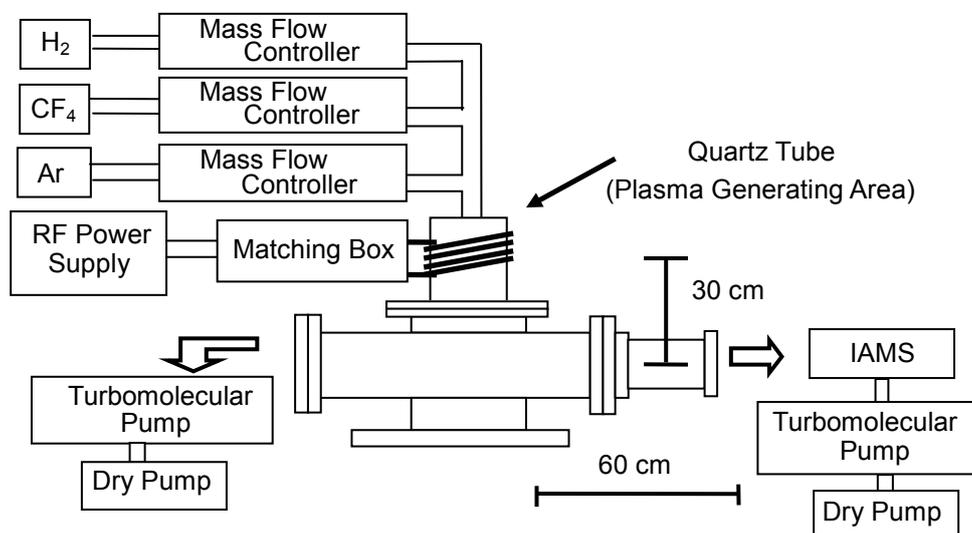


Fig. 1. Schematic view of the experimental setup.

13.56MHz) power of 150 W (ARIOS, ERFS-511). The produced positive ions were analyzed using a quadrupole mass spectrometer contained in a low-pressure Li⁺ attachment mass spectrometer (CANON ANELVA, L-241G-IA), which was separated by an aperture with 0.8 mm in diameter from a Li⁺ attachment compartment and was differentially pumped with a 220 l·s⁻¹ turbomolecular pump. This mass spectrometer can work as a normal mass spectrometer when the Li⁺ ion is not generated. Attaching the Li⁺ ion to neutral species allows the fragment-free mass analysis of the neutral species. The natural abundance of ⁶Li⁺ is 7.6%, and then would disturb the assignment of mass peaks observed through the Li⁺ ion attachment. This spectrometer contains a simple magnetic mass filter for selecting ⁷Li⁺, reducing the ⁶Li⁺/⁷Li⁺ ratio to 3.3%.

In ordinary ion-attachment ionization, a third body such as N₂ is additionally supplied into the ion attachment compartment at the order of 100 Pa to stabilize the ion-attachment products. In the present low-pressure type one, no third body is additionally supplied, allowing the mass analysis of the neutral species included in low-pressure (a few Pa) plasmas, although the probability of attaching Li⁺ is very low, especially in the small species that consist of less than ten atoms.

CF₄ (carbon tetrafluoride, 99.999%, TAKACHIHO TRADING), Ar (99.999%, NIPPON SANJO) and H₂ (99.999%, NIPPON SANJO) were supplied into the chamber using mass flow controllers (KOFLOC, 360). The pressure was measured with a ceramic capacitance gauge (PFEIFFER, CCR364) and a cold cathode gauge (BALZERS, KR260) in the chamber, and with an ionization gauge (ANELVA, MG-2F) in the mass spectrometer. The base pressure was 6×10⁻⁵ Pa in the

chamber and 1×10⁻⁷ Pa in the mass spectrometer. The operating pressure was 1.0 Pa and equal to that in the Li⁺ attachment compartment. The distance between the center of the plasma source and entrance of the mass spectrometer was 90 cm. Three grids were used only while observing neutral species by IAMS. These grids prevent excessive electrons and positive ions produced in the plasma from flowing into the Li⁺ ion attachment mass spectrometer. The DC voltages of 0, -71 and +79 V were applied to each of three grids in order of those close to the plasma, respectively.

We estimated reaction enthalpies by conducting the geometry optimization and frequency calculations under the B3LYP/6-31+G(d) level followed further by the same calculations under the B3LYP/6-311+G(3df) level with the GAUSSIAN03 program package [9] using a high performance server (IBM, eServer p5 model 595) set up in the Computing and Communication Center of Kyushu University.

3. Results and discussion

3.1 Mass spectra

Typical mass spectra of neutral species and positive ions observed in the downstream region of the Ar/CF₄/H₂ plasma are shown in Fig. 2. Neutral species were observed as their Li⁺ ion adducts. The plasma was generated under conditions of an RF power of 150 W, a pressure of 1.0 Pa, flow rates of 102 sccm for Ar, 31.5 sccm for CF₄ and 10 sccm for H₂. The abbreviation M_N means C_MF_NLi⁺ in Fig. 2a and C_MF_N⁺ in Fig. 2b. The superscript "O" and "H" means the presence of the O or H atom(s) in the species, for example, 2₄^{H2} = C₂F₄H₂Li⁺ in Fig. 2a and 4₇^O = C₄F₇O⁺ in Fig. 2b. We observed

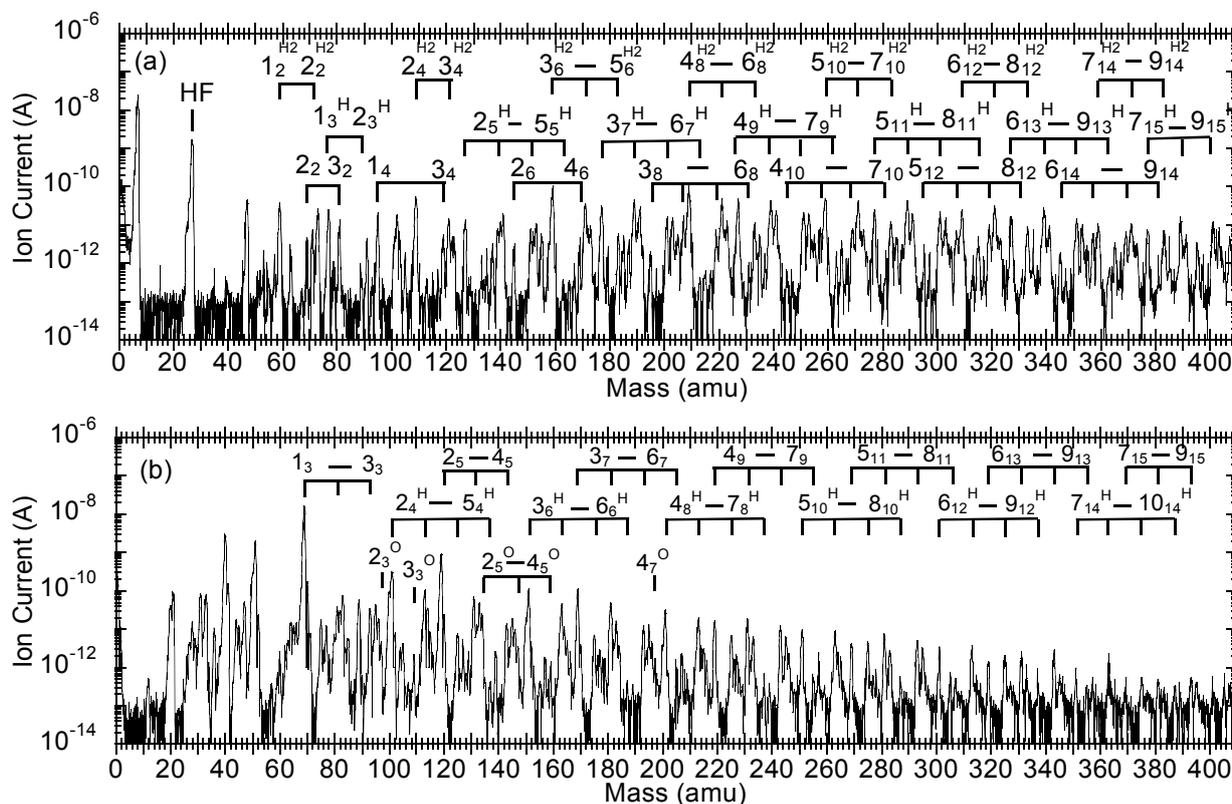


Fig. 2. Mass spectra of (a) the neutral species and (b) the positive ions observed in the downstream region of the Ar/CF₄/H₂ plasma generated at flow rates of 102 sccm for Ar, 31.5 sccm for CF₄ and 10 sccm for H₂.

neutral species containing up to 9 carbon atoms and positive ions up to 10 carbon atoms. Compared to the Ar/CF₄ plasmas, various unsaturated neutral species and positive ions appeared additionally in the Ar/CF₄/H₂ plasma.

3.2 Neutral species

All the observed neutral species are summarized in Table 1. We have previously found only C_nF_{2n+2} (n = 1–7) and C_nF_{2n} (n = 4–8) in the Ar/CF₄ plasmas [7]. In the Ar/CF₄/H₂ plasmas, a variety of species with more unsaturated chemical bonds, such as C_nF_{2n-2} and C_nF_{2n-4}, appeared. The H atom produced through the decomposition of the H₂ gas injected in the plasma would lead to the formation of C_nF_{2n-2} and C_nF_{2n-4} through the abstraction reaction of the F atom from C_mF_N. Hikosaka *et al.* [11] have reported that the CF₂ density were increased two orders of magnitude after the hydrogen injection, whereas the CF₃ density increased twice due to the abstraction reaction by the H atom from CF₃, CF₃ + H → CF₂ + HF, in the CF₄/H₂ plasma, in which the RF power was 50 W and the partial pressures of CF₄ and H₂ were 18.8 and 0.75 Pa, respectively. This result suggests the efficient F abstraction from relatively high-mass species. In addition, the concentration of the F atom in the plasma was reduced through the HF production, disturbing the formation of species with relatively high F/C ratios.

Table 1. Neutral species observed in the Ar/CF₄/H₂ plasma.

| species | range of n |
|---|------------|
| C _n F _{2n+2} | 1–7 |
| C _n F _{2n} | 4–8 |
| C _n F _{2n-2} | 3–8 |
| C _n F _{2n-4} | 3–9 |
| C _n F _{2n+1} H | 1–7 |
| C _n F _{2n-1} H | 2–8 |
| C _n F _{2n-3} H | 4–9 |
| C _n F _{2n-5} H | 5–9 |
| C _n F _{2n} H ₂ | 1–7 |
| C _n F _{2n-2} H ₂ | 2–8 |
| C _n F _{2n-4} H ₂ | 3–9 |

The reaction enthalpies summarized in Table 2 indicate that the abstraction reactions of the F atom from C_mF_n by the H atom are exothermic in the case of the number of carbon atoms being 3 and 4 and that the reactions can take place.

The formation of chemical species containing the hydrogen atom(s) would be due to the reactions, C_mF_n + H → C_{m-1}F_{n-2} + CF₂H, as the first step. The growth of CF₂H would lead to the various H-containing species. In addition, the abstraction of H from the H-containing species by the F atom would inhibit the formation of H-containing species with three or more H atoms.

Table 2. Enthalpy changes (Δ_rH^o) in some HF formation reactions estimated through the B3LYP/6-311+G(3df) level calculations.

| Reactions | Δ _r H ^o (kcal·mol ⁻¹) |
|--|--|
| C ₃ F ₈ + H → CF ₃ CF ₂ CF ₂ + HF | -54.5 |
| C ₃ F ₈ + H → CF ₃ CF ₂ CF ₃ + HF | -83.9 |
| CF ₃ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₃ + HF | -308.8 |
| CF ₃ CF ₂ CF ₃ + H → CF ₂ CF ₂ CF ₃ + HF | -279.4 |
| CF ₂ CF ₂ CF ₃ + H → CFCFCF ₃ + HF | -62.1 |
| CF ₂ CF ₂ CF ₃ + H → CF ₂ CF ₂ CF ₂ + HF | -83.0 |
| CFCFCF ₃ + H → CFCFCF ₂ + HF | -126.7 |
| CF ₂ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₂ + HF | -283.2 |
| CFCFCF ₂ + H → CFCFCF + HF | -32.5 |
| CF ₂ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₂ + HF | -68.3 |
| CFCFCF + H → CFCCF + HF | -299.5 |
| CF ₂ CF ₂ CF ₂ + H → CFCCF + HF | -86.3 |
| C ₄ F ₁₀ + H → CF ₃ CF ₂ CF ₂ CF ₂ + HF | -59.5 |
| C ₄ F ₁₀ + H → CF ₃ CF ₂ CF ₂ CF ₃ + HF | -95.8 |
| CF ₃ CF ₂ CF ₂ CF ₂ + H → CF ₃ CF ₂ CF ₂ CF ₂ + HF | -315.1 |
| CF ₃ CF ₂ CF ₂ CF ₃ + H → CF ₃ CF ₂ CF ₂ CF ₃ + HF | -301.1 |
| CF ₃ CF ₂ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₂ CF ₂ + HF | -46.8 |
| CF ₃ CF ₂ CF ₂ CF ₃ + H → CF ₃ CF ₂ CF ₂ CF ₂ + HF | -106.9 |
| CF ₃ CF ₂ CF ₂ CF ₂ + H → CF ₃ CF ₂ CF ₂ CF ₂ + HF | -272.7 |
| CF ₂ CF ₂ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₂ CF ₂ + HF | -329.1 |
| CF ₃ CF ₂ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₂ CF ₂ + HF | -93.7 |
| CF ₂ CF ₂ CF ₂ CF ₂ + H → CF ₂ CF ₂ CF ₂ CF ₂ + HF | -119.9 |
| CF ₂ CF ₂ CF ₂ CF ₂ + H → CFCFCF ₂ CF ₂ + HF | -70.2 |

Fig. 3a shows the intensity dependence of C_nF_{2n+2} (n = 2 and 4) and C_nF_{2n} (n = 4 and 6) on the flow rate of H₂ in the Ar/CF₄/H₂ plasmas. The pressure of Ar and CF₄ were 0.7 Pa and 0.3 Pa in these experiments, respectively. The intensity of C_nF_{2n+2} (n = 1 and 2) and C_nF_{2n} (n = 4 and 5) were increased with the flow rate of H₂. In contrast, the intensity of C_nF_{2n+2} (n > 2) and C_nF_{2n} (n > 5) were decreased or almost constant with increasing the flow rate of H₂.

The tendency of the plots shown in Fig. 3a can be reasonably explained by taking into account the F abstraction from C_nF_{2n+2} and C_nF_{2n} by the H radical as follows: The existence of various C_nF_{2n+2} and C_nF_{2n} in the Ar/CF₄ plasma [7] indicates that CF_x (x = 1–3) produced by the decomposition of CF₄ react to produce these high-mass species. Hikosaka *et al.* [12] have reported that the densities of CF_x increased by supplying H₂ in the Ar/CF₄ plasmas. Then, if there were no loss processes of C_nF_{2n+2} and C_nF_{2n} caused by the H₂ supply, the density of each C_nF_{2n+2} and C_nF_{2n} in the plasma should be increased with the H₂ flow rate. Actually, the F abstraction from C_nF_{2n+2} and C_nF_{2n} by the H radical can take place as their loss processes. The rate of the F

abstraction would be increased with the number of the F atoms contained in the reactants, C_nF_{2n+2} and C_nF_{2n}. Therefore, it is expected that the densities of C_nF_{2n+2} and C_nF_{2n} would be increased with the H₂ flow rate in the case of relatively small *n* because the formation of C_nF_{2n+2} and C_nF_{2n} would be prior to their loss. On the contrary, their loss processes would be prior to their formation in the case of relatively large *n*. In addition, the loss of C_nF_{2n} by the F abstraction would be reduced by the formation of C_nF_{2n} through the F abstraction from C_nF_{2n+2}.

The intensity dependence of C₄F₄ and C₄F₆ on the flow rate of H₂ is shown in Fig. 3b. The intensity of highly unsaturated species was increased with the flow rate of H₂ above a flow rate of 5 sccm. This finding strongly suggests that highly unsaturated species are produced by stepwise abstraction reactions of the F atoms from C_nF_{2n+2} and C_nF_{2n}.

3.3 Positive ions

All the observed positive ions are summarized in Table 3. We have previously found only C_nF_{2n+1}⁺ (*n* =

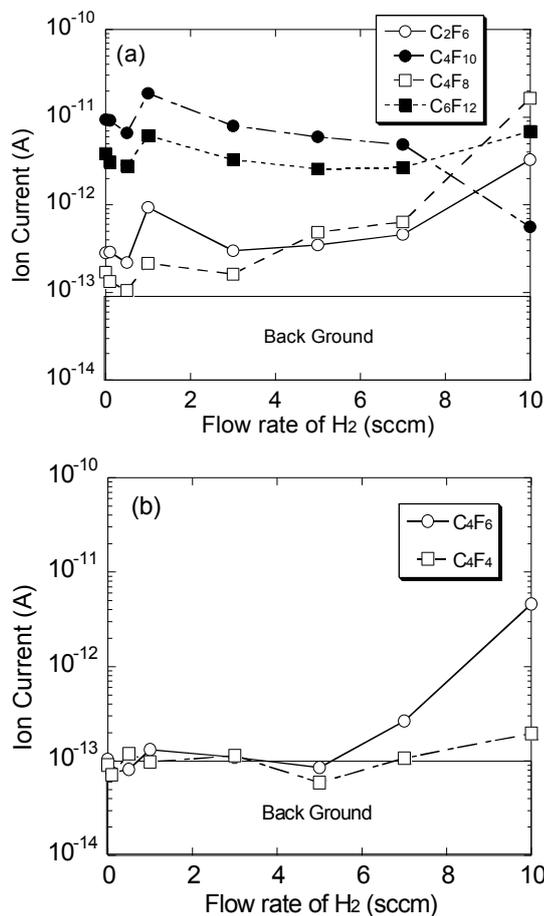


Fig. 3. Intensity dependence of the neutral species on the flow rate of H₂: (a) C_nF_{2n+2} (*n* = 2 and 4) and C_nF_{2n} (*n* = 4 and 6) and (b) C₄F₄ and C₄F₆.

1–7), C_nF_{2n-1}⁺ (*n* = 3–7), and C_nF_{2n-3}⁺ (*n* = 3–9) in the Ar/CF₄ plasmas. In the Ar/CF₄/H₂ plasmas, C_nF_{2n-5}⁺ (*n* = 5–10) appeared additionally. Furthermore, various positive ions containing the H atom appeared.

Table 3. Positive ions observed in the Ar/CF₄/H plasma. (N_M^H = C_MF_NH⁺)

| species | range of <i>n</i> |
|---|-------------------|
| C _n F _{2n+1} ⁺ | 1–7 |
| C _n F _{2n-1} ⁺ | 3–8 |
| C _n F _{2n-3} ⁺ | 3–9 |
| C _n F _{2n-5} ⁺ | 5–10 |
| C _n F _{2n} H ⁺ | 1–7 |
| C _n F _{2n-2} H ⁺ | 2–8 |
| C _n F _{2n-4} H ⁺ | 3–9 |
| C _n F _{2n-6} H ⁺ | 5–10 |

The intensity plots of the observed positive ions with respect to the mass number at 10 sccm H₂ flow rate are shown in Fig. 4. In the case of the Ar/CF₄ plasma, C₆F₉⁺ was maximal in intensity in the C_nF_{2n-3}⁺ series and the intensity was 1 × 10⁻¹² A. The C_nF_{2n-3}⁺ series remarkably increased the intensity in the Ar/CF₄/H₂ plasma, as shown in Fig. 4, although the intensity of the C_nF_{2n+1}⁺ and C_nF_{2n-1}⁺ series was similar to that in the Ar/CF₄ plasma. In particular, C_nF_{2n-3}⁺ (*n* = 3–5) were stronger than C₆F₉⁺. These findings suggest that the enhanced formation of relatively small C_nF_{2n-3}⁺ leads to the C_nF_{2n-5}⁺ formation.

We could not detect high-mass C_mF_n⁺ positive ions having even-numbered F atoms. This finding indicates that the stepwise F abstraction reactions from the C_nF_{2n+1}⁺ and C_nF_{2n-1}⁺ series by the H atom are negligible for the formation of C_nF_{2n-3}⁺ and C_nF_{2n-5}⁺.

There was an intensity alternation with carbon number in the C_nF_{2n-5}⁺ series, as shown in Fig. 4. This finding suggests that the formation of larger C_nF_{2n-5}⁺ is not due to the growth of smaller C_nF_{2n-5}⁺ but due to the reactions of reactants belonging to different series and that the reactivity of the reactants depends significantly on the parity of the number of carbon atoms contained in the reactants.

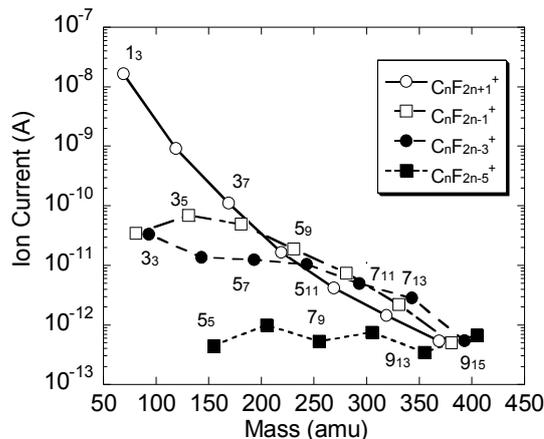


Fig. 4. Intensity plots of the positive ions observed in the downstream region of the Ar/CF₄/H₂ plasma with respect to mass number. The abbreviation M_N represents C_MF_N⁺.

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- [1] M. Sekine, *J. Plasma Fusion Res.* **83**, 319 (2007).
- [2] T. Fujii, *Chem. Phys. Lett.* **191**, 162 (1992).
- [3] T. Fujii and K. Syouji, *J. Appl. Phys.* **74**, 3009 (1993).
- [4] T. Fujii, *J. Appl. Phys.* **82**, 2056 (1997).
- [5] Y. Shikowa, M. Nakamura, H. Maruyama, Y. Hirano, Y. Taneda, M. Inoue and T. Fujii, *BUNSEKI KAGAKU* **53**, 475 (2004) [in Japanese].
- [6] M. Sablier, K. Iwase, G. Sato and T. Fujii, *Chem. Phys. Lett.* **409**, 342 (2005).
- [7] K. Furuya, S. Yukita, H. Okumura and A. Harata, *Chem. Phys. Lett.* **34**, 224 (2005).
- [8] K. Furuya, S. Yukita and A. Harata, *Jpn. J. Appl. Phys.* **45**, 5219 (2006).
- [9] M.J. Frisch *et al.*, GAUSSIAN 03, Revision D.01, Gaussian, Inc., Wallingford CT, 2004.
- [10] M. Nakamura, Y. Hirano, Y. Shiokawa, M. Takayanagi and M. Nakata, *J. Appl. Phys.* **74**, 3009 (2006).
- [11] Y. Hikosaka, H. Toyoda and H. sugai, *Jpn. J. Appl. Phys.* **32**, L690 (1993).
- [12] Y. Hikosaka, M. Nakamura and H. Sugai, *Jpn. J. Appl. Phys.* **33**, 2157 (1994)